

The Fine Line: Spring 2017 **Videos for the eBeam Community**

Shot Talk: A Word from Our Sponsor

Aki Fujimura, CEO of D2S, looks back at the recent SPIE Conference—including highlights of the annual eBeam Initiative luncheon—as well as previews what's new at Photomask Japan. English and Japanese versions of the video are available.



Leo Pang, chief product officer of D2S, also recaps these developments, as well as provides an update on the China Semiconductor Technology International Conference (CSTIC), in Chinese.



Tech Talk

Tom Cecil of Synopsys discusses the resurgence of inverse lithography technology (ILT), including what's driving the need for ILT, current use cases for design exploration, logic and memory, as well as future opportunities for supporting directed selfassembly (DSA) and EUV.



Perspectives

Greg McIntyre, director of advanced patterning at imec (one of the newest members of the eBeam Initiative), offers his thoughts on what it's like to work at one of the world's leading nanoelectronics R&D centers, as well as the importance of eBeam technology to lithography and mask making, what's driving up confidence in EUV, and the latest on imec's joint venture with JSR in EUV resist development.



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Shot Talk: Aki Fujimura, D2S



Shot Talk: Leo Pang, D2S



Tech Talk: Dr. David Lam, Multibeam



Perspectives: Brian Grenon, RAVE LLC

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The eBeam Initiative provides a forum for educational and promotional activities regarding new semiconductor manufacturing approaches based on electron beam (eBeam) technologies. Its goals are to reduce the barriers to adoption to enable more integrated circuit (IC) design starts and faster time-to-market while increasing the investment in eBeam technologies throughout the semiconductor ecosystem. For more information, please email requests@ebeam.org or visit www.ebeam.org